

- [54] **LIGHT-SENSITIVE IMAGE-FORMING MATERIAL**
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430/160
- [58] Field of Search ..... 430/271, 160, 155, 325,  
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[57] **ABSTRACT**

A light-sensitive image-forming material which comprises a support having provided thereon a first layer comprising at least one alcohol-soluble polyamide resin and, on said first layer, a second layer comprising a light-sensitive photoresist composition, said layer containing said alcohol-soluble polyamide resin containing one or more polymers having one or more of a free carboxy group(s), one or more of a phenolic hydroxy group(s) or a maleic anhydride group in a proportion of about 0.1:9.9 to 6:4 by weight to said polyamide resin.

**6 Claims, No Drawings**